

# INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

Sheet

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of

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## Complete if Known

Application Number	10/604,740
Filing Date	08/13/03
First Named Inventor	W. R. STOWELL et al.
Art Unit	2879-1746
Examiner Name	CARLILLO
Attorney Docket Number	124251

## U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No. <sup>1</sup>	Document Number		Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code <sup>2</sup> (if known)			
b2		US- 4,087,721		05/02/1978	Mourier	
		US- 4,098,450		07/04/1978	Keller et al.	
		US- 4,689,468		08/25/1987	Muehlberger	
		US- 4,851,636		07/25/1989	Sugimoto et al.	
		US- 4,877,937		10/31/1989	Müller	
		US- 4,975,147		12/04/1990	Tahara et al.	
		US- 5,356,478		10/18/1994	Chen et al.	
		US- 6,118,218		09/12/2000	Yializis et al.	
		US- 6,137,078		10/24/2000	Keller	
		US- 6,524,538	B2	02/25/2003	Barankova et al.	
		US-				
		US-				
		US-				

## FOREIGN PATENT DOCUMENTS

Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document			Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>
		Office <sup>3</sup>	Number <sup>4</sup>	Kind Code <sup>5</sup> (if known)				

## OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s) volume-issue number(s), publisher, city and/or country where published.	T <sup>7</sup>
b2		BRECELJ, F. et al., "Reduction of metal oxide thin layers by hydrogen plasma", Vacuum, 1990, pgs. 177-178, Vol. 40, Numbers 1/2, Pergamon Press plc (1990).	
b2		STURGES, D.J., et al., "A Qualitative Theory of the Medium Pressure Hollow Cathode Effect", Physica 37, pgs. 457-466	
b2		"13.56 MHz Hollow Cathode Plasma Source HCD L-300 by PlasmaConsult", pgs. 1-6, Nano-Master, Inc., Austin, TX	
b2		RUSCH, Bill, LPPS-RTA Process, Sulzer Metco (The Coatings Company), plasma-process.ppt (3 pages)	
b2		FRANCIS, Gordon, The Glow Discharge at Low Pressure, Encyclopedia of Physics, 1956, pgs. 53, 91, 97, 100-101	

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3/11/05